SHEET 1 OF 1

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INITIALS	PATENT NO.	DATE	NAME		CLASS	SUBCLASS	FILI	ING DATE	
T.A.C.	3,930,857	1/6/1976	Bendz et al.		430	313			
	5,111,240	5/5/1992	Boetiger et al.		355	53			
	5,252,415	10/12/199 3	Yoshizawa et al.		430	31			
	5,596,618	1/21/1997	Ogushi		378	0 34			
	5,648,860	7/15/1997	Ooi et al.		349	10		-	
	5,777,713	7/7/998	Kimura		349	156			
	5,978,062	11/2/1999	Liang et al.		349	155			
	6,028,659	2/22/2000	Kaneko		355	053			
	6,043,496	3/28/2000	Tennant		250	492			
7	6,087,274	7/11/2000	Tonucci et al.		438	758			
	6,187,486B1	2/13/2001	Lai et al.		430	22			
J	6,236,445B1	5/22/2001	Foschaar et al.		3119	156			
		FOR	EIGN PATE	NT DOCUMEN	TS				
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0	· ·	<del> </del>					n litho	graphy"	
T.R.C7	K. Ismail, "A noel method for submicron structurization using optical projection lithography", Microelectronic Engineering Vol.1, No. 4, pp. 295-300 (1983).  M.J. Cole et al., "Moving fiber/phase mask-scanning beam technique for enhanced flexibility in								
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producing fibre gratings with uniform phase mask", Electronic Letter, 17th Aug. 1995, Vol. 31, No. 17, pp. 1488-1490 (1995).									
1	O. Tabata et al., "Moving mask Liga (M <sup>2</sup> LIA) process for control of side wall inclination",								
Micro-Electro Mechanical System, 1999, MEMS 1999, The 12 <sup>th</sup> IEEE International Conference, pp. 252-256 (1999).									
EVAMINED (A) DATE CONSIDERED (									
6 homoly 09/25/03.									
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.